(Following Paper ID and Roll No. to be filled in your Answer Book)

PAPER ID : 3093　　Roll No.

B. Tech.

(SEM. VI) EXAMINATION, 2008-09
VLSI TECHNOLOGY AND DESIGN

Time : 3 Hours]　　　　　　　　　　　　*[Total Marks : 100*

Note : Attempt all questions.

1　Attempt any **four** parts of the following :　　5×4

　　(a)　How did technology shift from SSI to MSI then to VLSI?

　　(b)　Draw the equivalent circuit of a base diffused resistor showing all parasitic elements.

　　(c)　For a die size of 0.25inch × 0.25inch, calculate the number of dice in a 50 wafer lot of 6 in wafers.

　　(d)　How is single crystal grown? Describe one of the approaches that allow the crystal to be grown with a free surface.

　　(e)　A silicon wafer with p type doping 10^{15} is heated at 1000^0C for 1 hour in dry oxygen. How much oxide has been grown?

　　(f)　What are the techniques to form oxide layer? What are applications of oxide layer?

2   Attempt any **two** parts of the following :   10×2

    (a)   Discuss diffusion. Find diffusion constants for :

        (i)   interstitial diffusion

        (ii)   substitutional diffusion

    (b)   What do you mean by ion implantation? If an analyzing magnet bends the ion beam through 45^0 and L= r =50cm, find displacement D that would be seen if B_{10} is sent through the system when it is turned for B_{11} if the extraction potential is 2 kV, find the field required.

    (c)   Write short notes on :

        (i)   Photo mask and Photo resists

        (ii)   Photolithography techniques.

3   Attempt any **two** parts of the following :   10×2

    (a)   Explain with neat diagram the fabrication of BJT.

    (b)   (i)   Draw a CMOS inverter and explain its transfer characteristics

        (ii)   What are different scaling methods? Write the various scaling factors for the device

    (c)   Describe the lambda design rules and layout methodology for CMOS circuit design.

4   Attempt any **four** parts of the following :   5×4

    (a)   Discuss the tests for stuck open faults for each transistor in a **two** input NOR gate.

    (b)   Which language is used to CAD design for VLSI? Discuss its application is design of MUX.

(c) Draw a stick diagram for a two input multiplexed latch. Place the two transmission gate side by side.

(d) Draw the circuit diagram of one stage of a dynamic CMOS register.

(e) Sketch the circuit diagram of a ratio less MOS inverter. Explain its operation.

(f) Draw the block diagram of 1 bit SRAM.

5   Attempt any **two** parts of the following :   10×2

(a) Discuss programmable logic array (PLA) with example of NMOS PLA.

(b) Describe field programmable gate array (FPGA). Realize NAND/NOR function using PGA?

(c) Describe the commonly used VLSI testing procedures.